

DERWENT-ACC-NO: 2003-633521

DERWENT-WEEK: 200482

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TITLE: Semiconductor fabricating apparatus for supplying process gas to inside of tube

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PRIORITY-DATA: 2001KR-0070682 (November 14, 2001)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES
MAIN-IPC KR 444753 B H01L 021/205	August 21, 2004	N/A	000
KR 2003039670 A H01L 021/205	May 22, 2003	N/A	001

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO	APPL-
DATE KR 444753B November 14, 2001	N/A	2001KR-0070682	
KR 444753B KR2003039670A	Previous Publ. N/A	KR2003039670 2001KR-0070682	N/A
November 14, 2001			

INT-CL (IPC): H01L021/205

ABSTRACTED-PUB-NO: KR2003039670A

BASIC-ABSTRACT:

NOVELTY - A semiconductor fabricating apparatus for supplying process gas to the inside of a tube is provided to rapidly exhaust reaction gas and minimize generation of particles by making the flow path of the reaction gas short, and to improve uniformity by uniformly supplying the reaction gas regardless of the position in a process chamber.

DETAILED DESCRIPTION - A plurality of wafers are loaded into a boat(140). A reaction furnace has a closed inner space into which the boat is loaded. A

shower head(120) uniformly sprays the reaction gas on the inner space of the reaction furnace, installed in the sidewall of the reaction furnace.

CHOSEN-DRAWING: Dwg.1/10

TITLE-TERMS: SEMICONDUCTOR FABRICATE APPARATUS SUPPLY PROCESS GAS TUBE

DERWENT-CLASS: U11

EPI-CODES: U11-C01B;

